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REPLY UNDER 37 C.F.R. § 1.116
EXPEDITED PROCEDURE
TECHNOLOGY CENTER ART UNIT 1763

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
HONGO, T.

Application No.: 09/536,721

Confirmation No. 5386

Filed: March 28, 2000

Group: 1763

Title: MICROWAVE PLASMA PROCESSING APPARATUS FOR
CONTROLLING A TEMPERATURE OF A WAVELENGTH
REDUCING MEMBER

Examiner: CROWELL, A.

135 NE
2/14/03
NW

* * * *

February 11, 2003

RESPONSE UNDER 37 C.F.R. § 1.116

Hon. Commissioner of Patents
Washington, DC 20231

Sir:

Responsive to the Office Action dated November 13, 2002, please consider the following remarks:

REMARKS

Claims 1-25 are pending in this application. Claims 10-17 have been withdrawn from consideration.

Claim Rejections – 35 U.S.C. § 112

Claims 2 and 3 have been rejected under 35 U.S.C. § 112, second paragraph.

Claim 2 recites, *inter-alia*, “wherein the first temperature control device controls the temperature of the slot electrode to be in a predetermined temperature range so as to substantially eliminate influence of water released from components in the process chamber on a substrate being processed.” One of ordinary skill in the art would understand that the